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PATENT

Attorney Docket No. QCS-003DV

JC979 U.S. PTO
09/974024

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT(S): Kamieniecki
SERIAL NO.: Not yet assigned GROUP NO.: Not yet assigned
FILING DATE: October 10, 2001 EXAMINER: Not yet assigned
TITLE: APPARATUS AND METHOD FOR REAPID PHOTO-THERMAL
SURFACE TREATMENT

INFORMATION DISCLOSURE STATEMENT

Box Patent Application
Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. §1.97, Applicants hereby make of record the references listed on the accompanying Form PTO-1449 for consideration by the Examiner in connection with the examination of the above-identified patent application. Per 37 C.F.R. §1.98 (d), copies of references are not enclosed for references previously submitted to the Office, or cited by the Office, in prior application 09/003,670, which was filed on January 7, 1998, and is relied on for an earlier filing date under 35 U.S.C. 120. Applicant will supply a copy of references previously submitted to the Office, or cited by the Office, in prior application 09/003,670, if requested to do so.

REMARKS

In accordance with the provisions of 37 C.F.R. §1.97, this statement is being filed (CHECK ONE):

- ☒ (1) within three (3) months of the **Filing Date** or before the mailing date of the **First Office Action** on the merits; or
- ☐ (2) after the period defined in (1) but before the mailing date of a **Final Rejection** or **Notice of Allowance**, and
- ☐ the requisite Statement is below, **OR**
- ☐ the requisite fee under Rule 1.17(p), namely **\$240.00**, is included herein, or

- ☐ (3) after the mailing date of a **Final Rejection** or **Notice of Allowance** but before the payment of the **Issue Fee**, **AND**
- ☐ Applicant hereby Petitions the Commissioner to accept and consider the attached Information Disclosure Statement, **AND**
- ☐ the requisite Statement is below, **AND**
- ☐ the requisite petition fee due under Rule 1.17(i)(I), namely **\$130.00** is included herein.

It is respectfully requested that each of the references shown on the attached Form PTO-1449 be made of record in this application.

STATEMENT

As required under §1.97(e), Applicants, through the undersigned, hereby state either that [check the appropriate space]:

- ☐ 1. [E]ach item of information contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application **not more than** three months prior to the filing date of the Information Disclosure Statement; or
- ☐ 2. [N]o item of information contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and to the knowledge of the person signing this Statement after making reasonable inquiry, no item of information contained in the Information Disclosure Statement was known to **any** individual designated in §1.56(c) **more than** three months prior to the filing of the Information Disclosure Statement.

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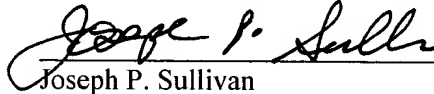
FEE AUTHORIZATION

Should any fee associated with the submission of this paper not be attached hereto as a check, the Commissioner is authorized to charge the missing fee to our Deposit Account, No. 20-0531. Any overpayments should be credited to said Deposit Account.

Respectfully submitted,

Date: October 10, 2001
Reg. No. 45,349

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FORM PTO - 1449

INFORMATION DISCLOSURE STATEMENT

ATTY DOCKET NO.: QCS-003DV

APPLICANT: Kamieniecki

SERIAL NO.: Not yet assigned

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U.S. PATENT DOCUMENTS

EXAM. INIT.	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	4,544,887	10/01/85	Kamieniecki	324	158	10/21/82
	4,558,660	12/17/85	Nishizawa et al.	118	725	3/16/83
	4,581,578	04/08/86	Honma et al.	324	158	01/31/84
	4,599,558	07/08/86	Castellano, Jr. et al.	324	158	12/14/83
	4,871,417	10/3/89	Nishizawa et al.	156	640	6/30/87
	5,306,671	04/26/94	Ogawa et al.			
	5,453,702	09/26/95	Goldfarb	324	765	11/29/93
	5,470,799	11/28/95	Itoh et al.	437	238	4/24/89
	5,471,293	11/28/95	Lowell et al.	356	30	02/02/94
	5,663,657	09/02/97	Lagowski et al.	324	766	09/26/94
	5,661,408	08/26/97	Kamieniecki et al.	324	765	03/01/95
	5,716,495	2/10/98	Butterbaugh et al.	156	643.1	3/25/96

FOREIGN PATENT DOCUMENTS

EXAM. INIT.	DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG Y/N
	41 22 587	01/23/93	DE					N
	WO 94/23854	10/27/94	PCT					Y

OTHER ART, JOURNAL ARTICLES, ETC.

EXAM. INIT.	OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication)
	Akazawa et al., "Photostimulated Evaporation of SiO ₂ and Si ₃ N ₄ Films by Synchrotron Radiation and its Application for Low-Temperature Cleaning of Si Surfaces", <i>Journal of Vacuum Science and Technology</i> , Vol. 9, No. 5, September 1, 1991, pp. 2653-2661
EXAMINER	
DATE CONSIDERED	

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